

ABSTRACT OF THE DISCLOSURE

A pellicle is used for a photolithographic patterning process using a light having a wavelength of from 100 to 200 nm. The pellicle contains a pellicle membrane containing (A) a substantially linear fluoropolymer which has an alicyclic structure in its main chain, the main chain being a chain of carbon atoms, and the fluoropolymer satisfying the following requirements (1) the carbon atoms in the main chain of the fluoropolymer contain a carbon atom having at least one hydrogen atom bonded thereto and a carbon atom having no hydrogen atom bonded thereto; and (2) in the measurement of a high resolution proton magnetic resonance spectrum of the fluoropolymer, a number of hydrogen atoms based on signals appearing on a magnetic field side higher than 2.8 ppm, is at most 6 mol% based on a total number of hydrogen atoms.